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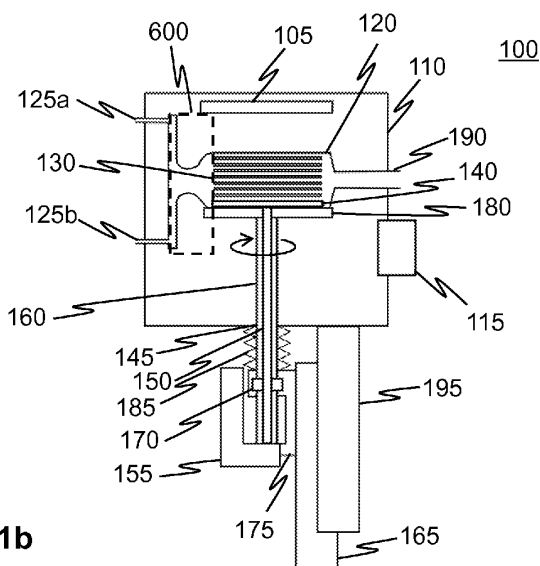


Fig. 1b

(57) Abstract: A substrate processing apparatus (100) that includes a reaction chamber (120) for accommodating substrates (130) arranged with their surfaces facing each other, a fluid distributor (600) for establishing a laminar fluid flow propagating from an entrance to the reaction chamber (120) through the length of the reaction chamber (120) and between the substrate surfaces, and a liftable substrate rotating system (500) configured to transfer the substrates (130), in a direction perpendicular to the substrate surfaces, between a loading position and a processing position and to rotate the substrates (130) in the processing position within the reaction chamber (120).

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